

6/20/03
#17(Amdt)
RPATENT
Docket No. 150.00800102JUN 23 2003
TC 1700

FAX RECEIVED

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Brian A. Vaartstra) Group Art Unit: 1756
 Serial No.: 09/651,702) Examiner: N. Barreca
 Confirmation No.: 2471)
 Filed: August 30, 2000)
 For: SUPERCritical COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL
AND METHODS OF USING SAME

AMENDMENT AND RESPONSE

Assistant Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed March 20, 2003, please amend the above-identified application as follows:

In the Specification

Please replace the paragraph beginning at page 25, line 5 (i.e., Abstract of the Disclosure), with the following rewritten paragraph. Per 37 C.F.R. §1.121, this paragraph is also shown in Appendix A with notations to indicate the changes made.

-A method for removing organic material in the fabrication of structures includes providing a substrate assembly having an exposed organic material and removing at least a portion of the exposed organic material using a composition including sulfur trioxide (SO₃) in a supercritical state. For example, the exposed organic material may be selected from the group of resist material, photoresist residue, UV-hardened resist, X-ray hardened resist, carbon-fluorine containing polymers, plasma etch residues, and organic impurities from other processes.
Further, organic material removal compositions for performing such methods are provided.